This project has received funding from the Electronic Components and Systems for European Leadership Joint

Undertaking under grant agreement No 876925





Al for New Devices And Technologies at the Edge

D2.4 Bitcell level device and selector integration

Deliverable No.	D2.4	Due Date	31-May-2021
Туре	Report	Dissemination Level	Confidential
Version	3.0	Status	Final
Description	This deliverable reports the development of memory and selector integration at bitcell level for PCM, OxRAM, SOT-MRAM, FeFET, TFT.		
Work Package	WP2 – New memory technologies for AI applications.		

PROPRIETARY RIGHTS STATEMENT

This document contains information, which is proprietary to the ANDANTE Consortium.

Neither this document nor the information contained herein shall be used, duplicated or communicated by any means to any party, in whole or in parts, except with prior written consent of the ANDANTE consortium.



Abstract (Published Summary)

As part of the Work package 2 dedicated to the enablement of new memory technologies and the demonstration of their scalability and array capacity for larger scale Artificial Intelligence (AI) applications, the deliverable 2.4 focus on the bit cell level device and selector integration for Magnetic Random Access Memory (MRAM), Ferroelectric Field-Effect Transistor (FeFET) based Memory, Oxide Random Access Memory (OxRAM) and Phase Change Random Access Memory (PCRAM). For these two last types of Resistive Memories (RRAM) the report gives a status on the development of materials and their first integration as backend selector associated to these memories in a crossbar array architecture in order to allow implementation of high-density memory.

CEA enabled the integration in a crossbar architecture of resistive memories such as OXRAM and PCRAM by demonstrating a chalcogenide Ovonic Threshold Switch (**OTS**) Backend selector directly fabricated near a RRAM device.

IMEC developed a Spin Orbit Torque Magnetic Memory device capable of <1ns switching in 300mm toolset.

Fraunhofer developed a ferroelectric FET (**FeFET**) with both Si channel and Indium-Gallium-Zinc-Oxide (**IGZO**) **material**, which opens possibilities to cointegrate this device not only in front-end but also in the backend of line of a logic node.